

**AMENDMENTS TO THE SPECIFICATION**

Please replace the paragraph beginning at page 24, line 21, which starts with "When the gas . . ." with the following amended paragraph.

When the gas containing no CF<sub>4</sub> gas, i.e., the gas containing no halogen atom, was caused to contain N<sub>2</sub> gas, the intensity ratio A/B did not attain a maximum value, thereby failing to yield a value exceeding the intensity ratio A/B caused by the emission of a plasma which was 100% oxygen as can be seen from FIG. 6. When the gas containing CF<sub>4</sub> gas was caused to contain N<sub>2</sub> gas, by contrast, a maximum value was obtained at an appropriate value. These facts have revealed that desirable etching in this embodiment cannot be realized when N<sub>2</sub> gas is simply added to O<sub>2</sub> gas, but a diamond product having a substantially perpendicular side face and a flat etching face can be obtained when N<sub>2</sub> gas is added to a mixed gas containing O<sub>2</sub> gas and [N<sub>2</sub>] CF<sub>4</sub> gas.